

ABSTRACT

The present invention has an object of the present invention to provide a polyvinyl acetal resin for heat-developable photosensitive materials as well as a
5 heat-developable photosensitive material while solving such problems as coating solution pot life, coloration of heat-developable photosensitive material, fog, poor gradation, insufficient sensitivity and poor undeveloped film storability and making it possible for the materials to acquire good image
10 characteristics.

The present invention is constituted of a polyvinyl acetal resin for heat-developable photosensitive materials which is a polyvinyl acetal resin synthesized by the acetalization reaction between a polyvinyl alcohol and an
15 aldehyde and

which comprises having a degree of polymerization of 200 to 3,000, a residual acetyl group content of 0 to 25 mole percent and a residual hydroxyl group content of 17 to 35 mole percent, as calculated while regarding one acetal group as two acetalized
20 hydroxyl groups, a water content of not more than 2.5% by weight and a residual aldehyde content of not more than 10 ppm and is free of any antioxidant.